

Supporting Information

Aerosol assisted CVD of thioether functionalised indium aminoalkoxides

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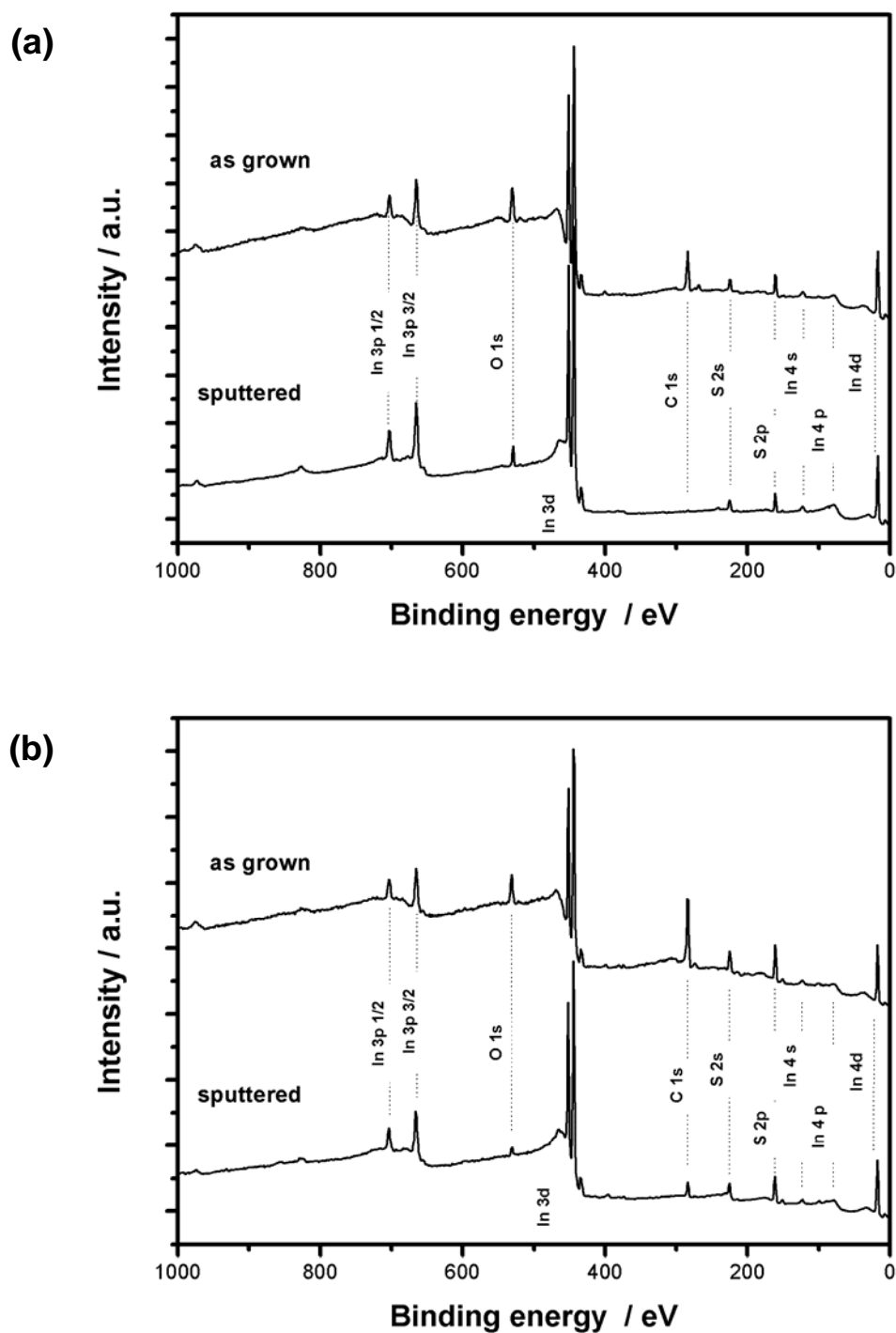


Figure S1: XPS survey of films obtained by AACVD using **In1** grown at (a) 400 °C before and after sputtering and (b) using **In4** 400 °C before and after sputtering. Spectra measured with Al K α radiation at room temperature.

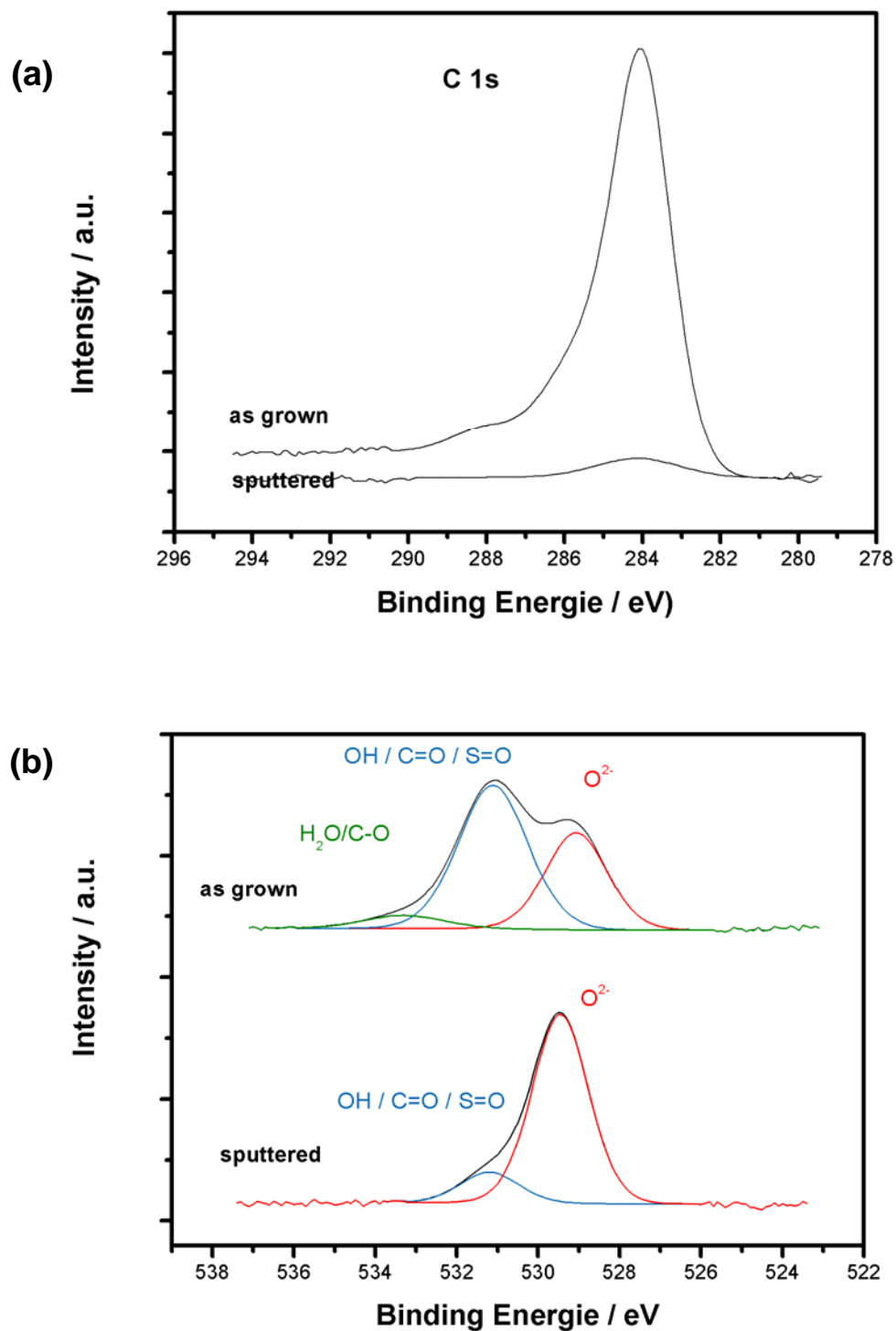


Figure S2: XPS spectra of the (a) C1s peak and (b) O1s peak of CVD deposits using **In1** at 400°C before and after sputtering recorded with an Al K α lab source.